

# **Future of Power Efficient Processing**



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**Microsystems Technology Symposium**  
**San Jose, CA**  
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# Power Efficient Electronics are Critical to Many DoD Missions



**Soldiers carry packs in 70-120 lbs range  
Frequently 10-20 lbs are batteries!**

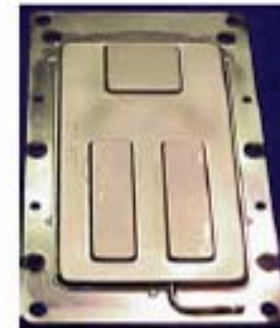


**Power is frequently  
scarce and expensive:  
UAVs, remote sensor  
networks, space, etc.**



DSRC Summer 2006  
Low Power Workshop

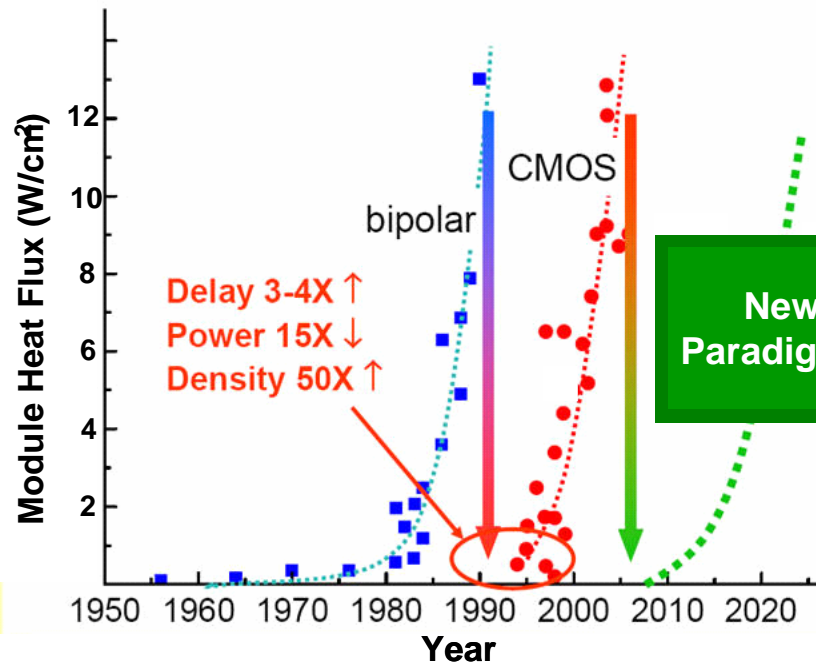
**Getting rid of dissipated heat  
is often a major problem by itself!**



Heat pipes



# Electronics History: Power Efficiency Perspective



$$\text{Power} = \text{Dynamic} + \text{Static} \\ = 0.5CV_{dd}^2f + I_{leak}V_{dd}$$

Ultimate Goals:

Decades power reduction  
No performance penalty

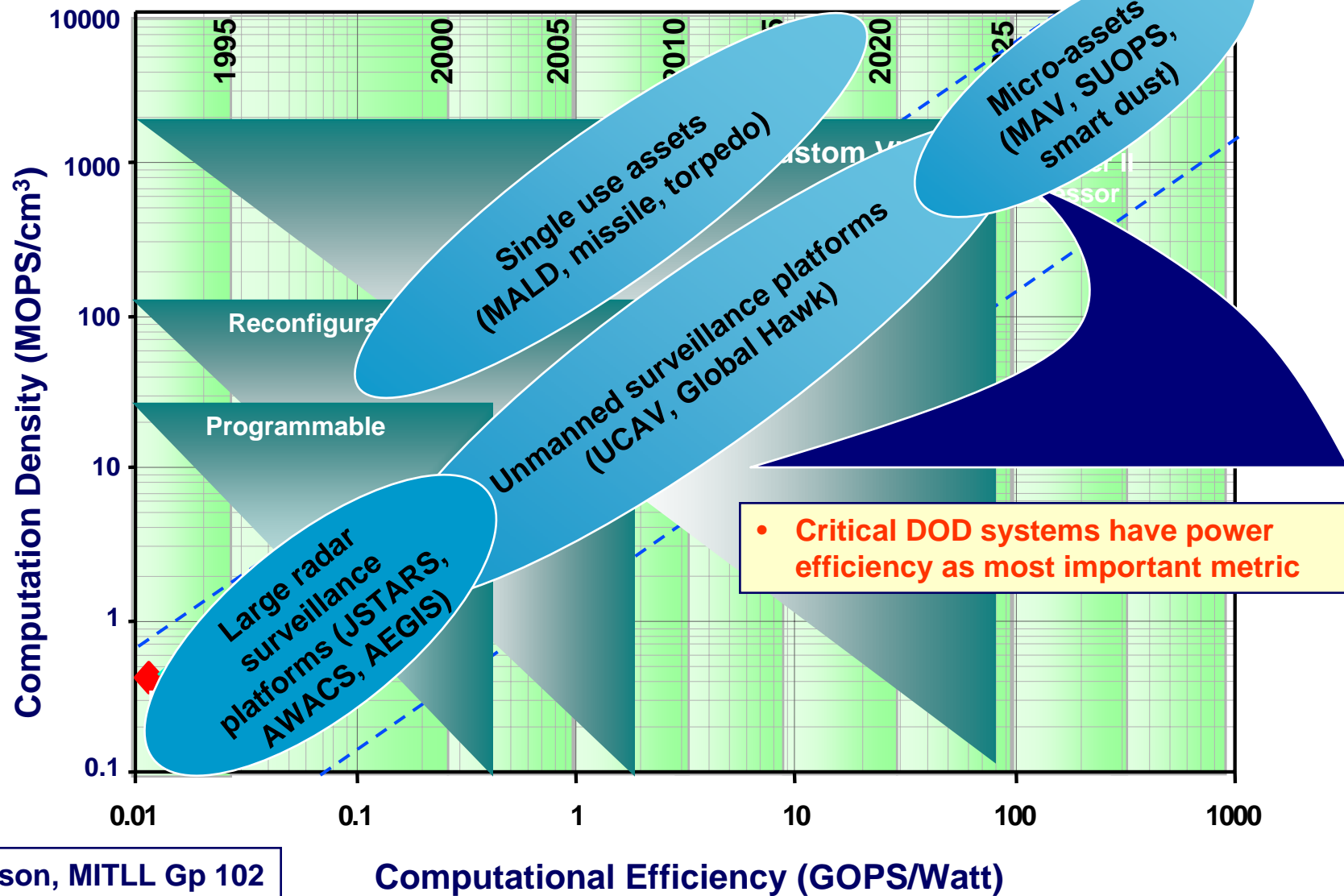
- Each technology ultimately reaches integration density limited by power dissipation
- Quantum jump then occurs to new technology with lower power

*Time for the next paradigm change ?*



# Embedded Computing for DoD

## Power Efficiency (Ops/Watt) is Key



J. Anderson, MITLL Gp 102  
HPEC Conference '04-'05



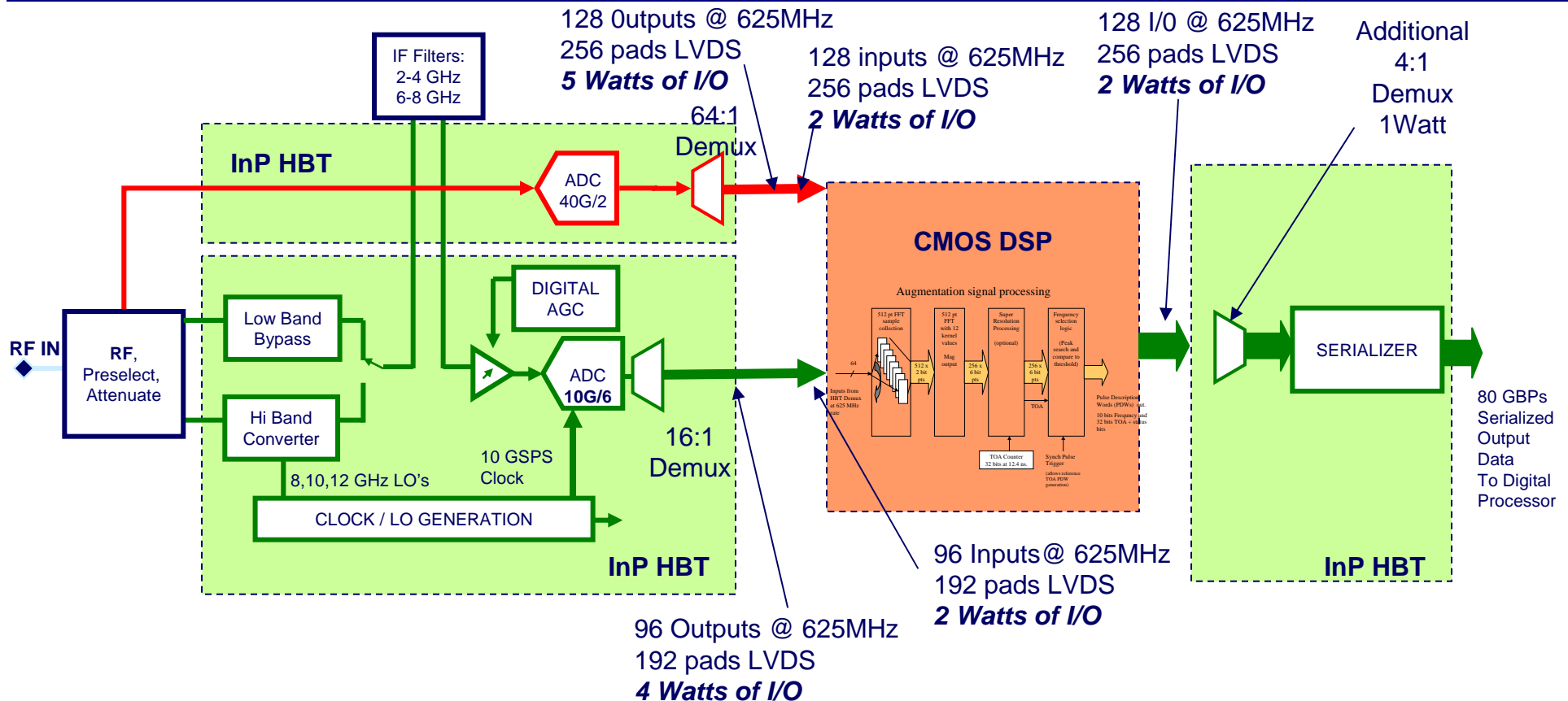
# Some Paths Forward: Power Efficiency



- **I) Densely integrated RF technology**
  - RF SOC vs MCM implementation
  - 'TEAM'
- **II) Novel Architecture/Design**
  - Power management
  - Sub-threshold , Parallelism, 3D
  - 'ESE', '3D-IC'
- **III) Ultra-low power CMOS**
  - Tunable threshold
  - Steeper sub-threshold slope ( $< 62$  mV/dec)
  - 'STEEP' BAA coming out
- **IV) Beyond Silicon**
  - Carbon electronics
  - Graphene, Nanotubes
    - Workshop in early April



# Power Benefits of Integration: RF-SOC vs. MCM



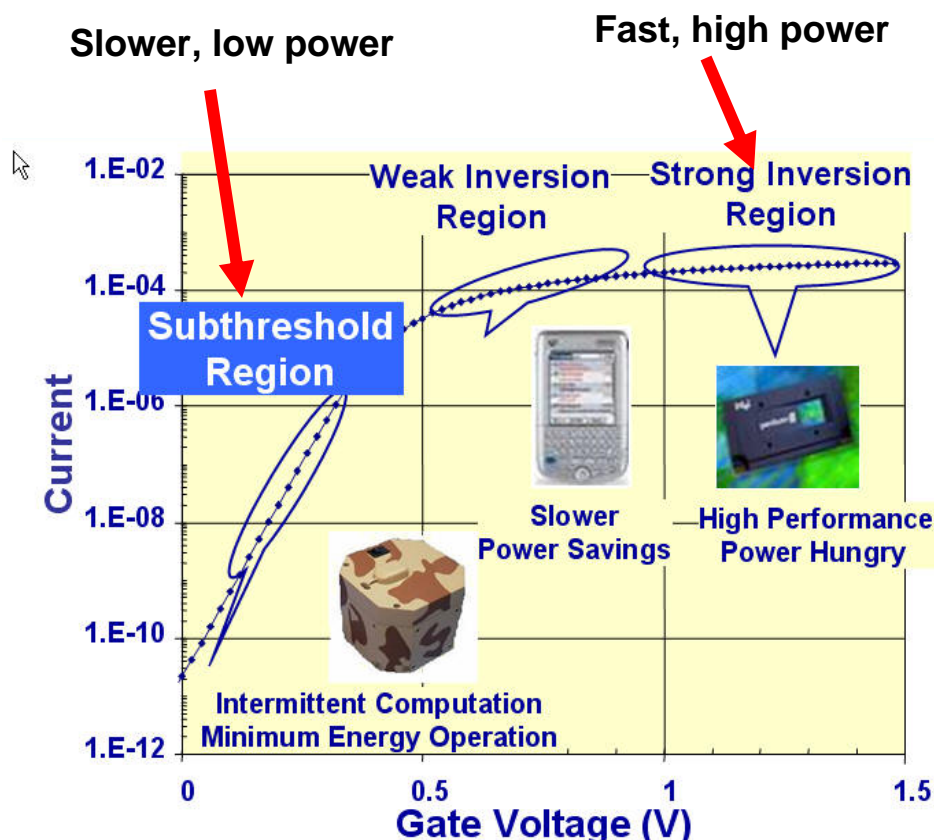
*All four ICs can be implemented in a single SiGe IC*

**... 16 Watts of additional power due to intra-chip I/O in multi-chip approach over a monolithic implementation**





# Sub-threshold Digital Design: Energy Starved Electronics (ESE) Program



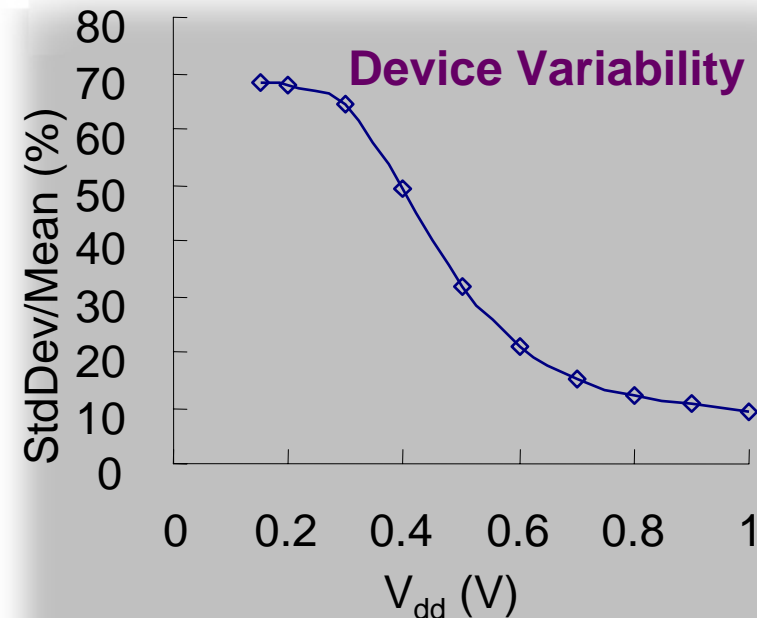
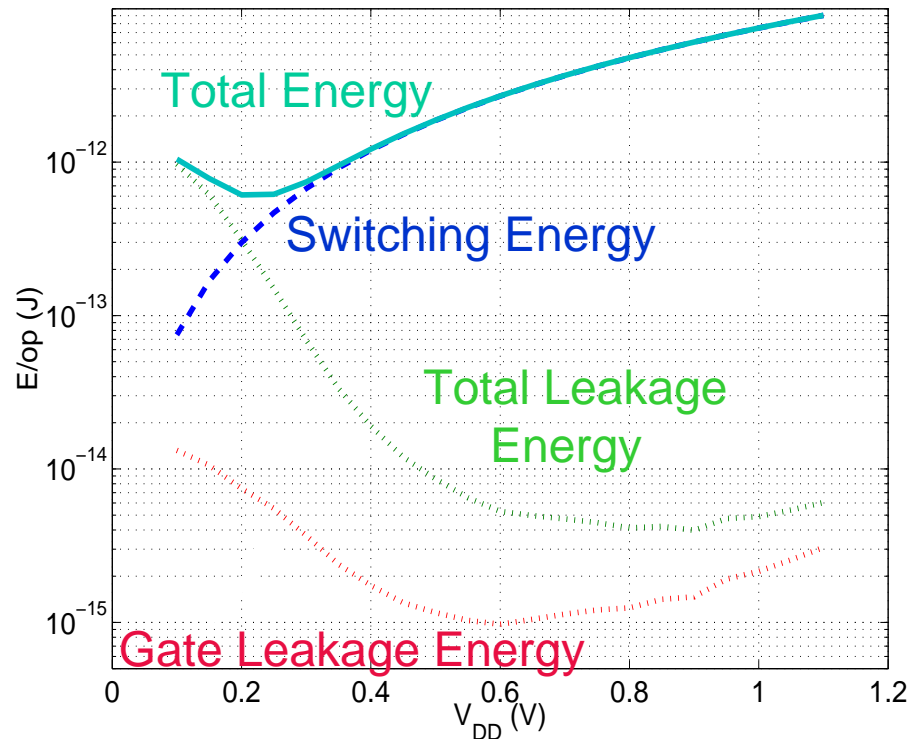
- Goal: Enable ultra-low power digital circuits operating in the *sub-threshold regime* while maintaining adequate performance. Energy consumption savings > 10X.
- Technical Challenges:
  - Develop standard cells operating at  $V_{dd} < 300$  mV; esp. SRAM
  - Achieving adequate performance (through parallelism)
  - Addressing high sensitivity to variations (via ECC)
- Design Only Approach:
  - No device technology changes
  - Exploits massive investment by industry for DoD benefit

PI: Prof. Anantha Chandrakasan, MIT  
Fab: TI, Dr. Dennis Buss, 65-nm CMOS





# Minimum Energy Point: Switching vs. Leakage



- Minimum energy point  $\approx 200$  mV (sub-threshold regime)
  - Must be compensated for (e.g., parallelism and threshold control)
  - Optimum voltage  $V_{dd}$  varies with circuit activity
- Leakage energy increases at extremely low voltages (long delay times)
- Increased variability requires wider margins, reduced performance

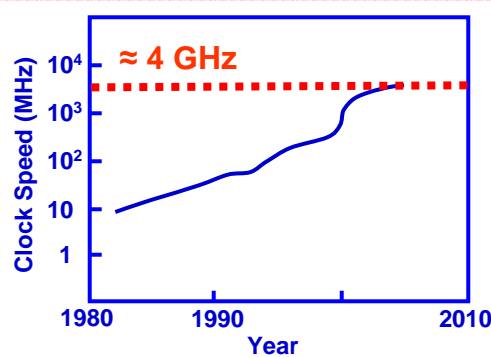


# Steep-subthreshold-slope Transistors for Electronics with Extremely-low Power (STEEP)

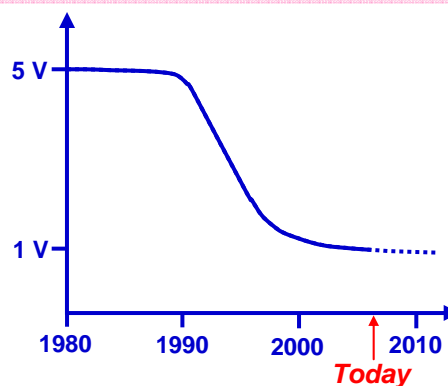


**Problem: Device Scaling alone will no longer meet DoD needs!**

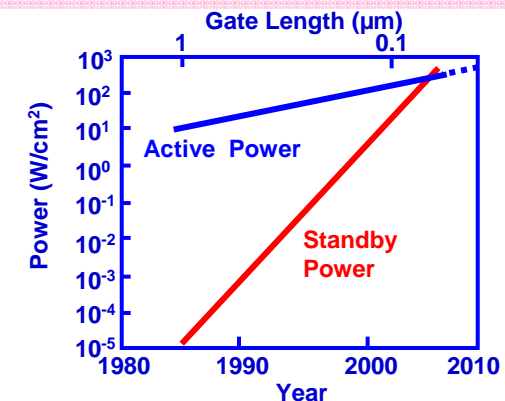
## Processor speed stalled



## Supply voltage stalled

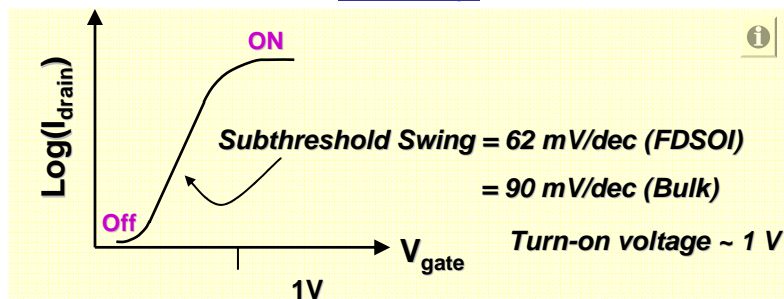


## Large leakage current increase



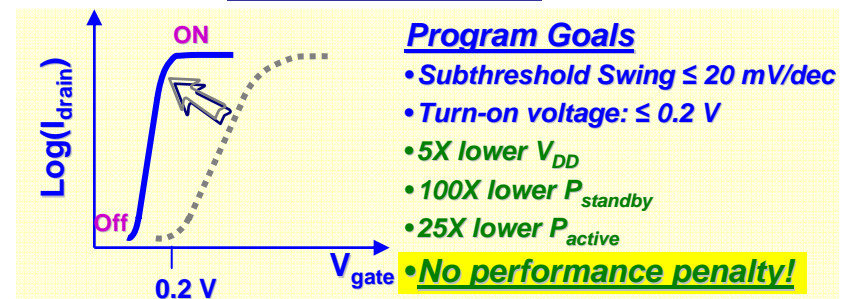
## Proposed Solution: Steep-subthreshold-slope Transistors

### Today



Theoretical minimum of the subthreshold swing of MOSFET is  $\ln 10(kT/q)$  or 60 mV/dec

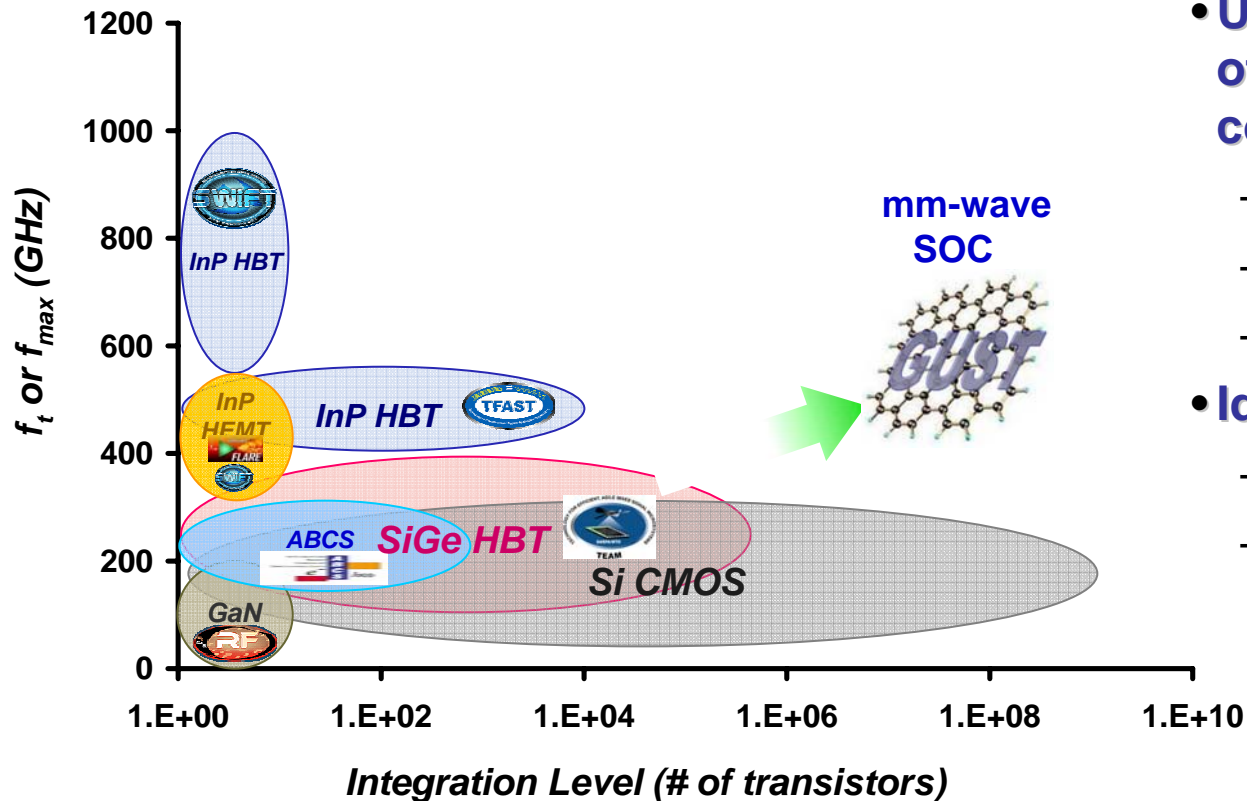
### STEEP Vision



Develop ideal transistor switch for ultra-low power electronics



# Carbon Electronics: High Performance & Integration for RF-SOC's



- Ultimate performance limits of mm-wave devices (radar, comms, etc):
  - *Higher speeds*
  - *Improved power efficiency*
  - *Lower “SWAP”*
- Ideal mm-wave device
  - *Key parameters*
  - *Integration path with Si*

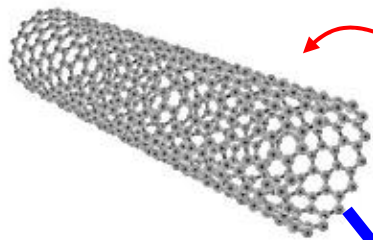
***New Opportunity: Carbon-based mm-wave SOC's***



# New Approach For Ideal mm-wave Material: Planar Carbon (Graphene)



## Carbon Nanotube



Challenges:

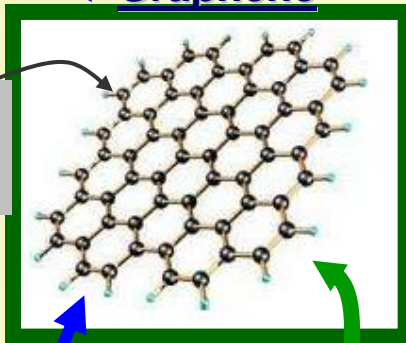
**Placement  
&  
Uniformity**

unroll

## Graphene

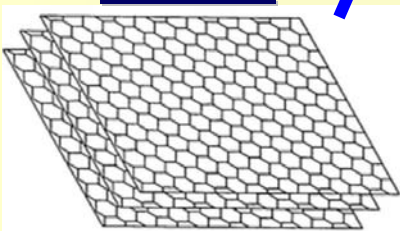
Planar system

$sp^2$  hexagonal  
 $a=0.25\text{nm}$ ,  $c=0.67\text{nm}$   
2D physics



"scrape"

## Graphite



**Planar form has most of  
the desirable properties  
of nanotubes**

## Graphene Properties:

- High mobilities for both electron & hole ( $> 10\text{X}$  silicon)
    - $\mu \geq 15,000 \text{ cm}^2/\text{Vs}$ ,  $m^* = 0.06m_0$
    - mm-wave & low power potential
    - High current density
  - Ideal electrostatics ("monolayer-on-insulator")
    - Sub-nm thickness
      - $< \text{Debye screening length}$
    - Enables aggressive scaling
  - Planar processing can be used
    - Standard paradigm
    - Straightforward integration with CMOS
- Semimetal band structure
- $I_{\text{on}}/I_{\text{off}} \sim 30$ , useful for RF devices

**Graphene is very promising material for mm-wave RF-SOC technology**



# A Possible Path Forward

